

What is claimed is:

1. A liquid processing apparatus for forming a coating film on a polygonal substrate by spin coating in an ambient 5 with a descending clean air flow, comprising:

a spin chuck including a support plate for substantially horizontally supporting the substrate thereon, the spin chuck rotating the substrate in a substantially horizontal plane;

10 a cup disposed around the substrate supported on the spin chuck;

an exhaust unit for evacuating an inside of the cup;

a supply nozzle for supplying a coating solution to a top surface of the substrate supported on the spin chuck;

15 and

at least one air flow control member provided on the spin chuck, the air flow control member being disposed adjacent to a periphery of the polygonal substrate supported on the spin chuck, wherein the air flow control member is 20 not provided near corner portions of the substrate supported on the spin chuck.

2. The liquid processing apparatus of claim 1, wherein a top surface of the air flow control member is substantially 25 at the same level as that of the substrate supported on the spin chuck.

3. The liquid processing apparatus of claim 1, wherein
the air flow control member includes a portion facing the
periphery of the substrate and a flat portion outwardly
5 extending from the portion facing the periphery of the
substrate.

4. The liquid processing apparatus of claim 1, wherein
the air flow control member includes an arc shaped outer rim.

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5. The liquid processing apparatus of claim 1, further
comprising a plurality of upright walls facing sides of the
polygonal substrate, respectively, wherein the upright walls
are disposed between the air flow control member and the
15 support plate along the sides of the polygonal substrate
supported on the spin chuck.

6. The liquid processing apparatus of claim 1, wherein
the support plate has a generally polygonal shape
20 corresponding to the substrate, and is provided with cutout
at corners thereof, the corner portions of the substrate
outwardly protruding from the support plate through the
cutout portions thereof when the substrate is supported on
the spin chuck.

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7. The liquid processing apparatus of claim 6, further

comprising a transfer arm having a number of support extrusions for supporting the corner portions of the substrates, respectively, wherein the transfer arm unloads the substrate from the spin chuck by supporting the 5 protruded corner portions of the substrate by the support extrusions.

8. The liquid processing apparatus of claim 6, wherein a size of each of the cutout portions ranges from about 4 mm 10 to 10 mm.

9. The liquid processing apparatus of claim 1, wherein the support plate includes at least one ventilation hole formed therethrough, the ventilation hole communicating with 15 the exhaust unit.

10. The liquid processing apparatus of claim 9, wherein the ventilation hole is provided at locations corresponding to corner portions of the substrate supported on the spin 20 chuck, as viewed from above.

11. The liquid processing apparatus of claim 1, further comprising:

25 a ring plate for controlling the descending clean air flow towards the substrate supported on the spin chuck; the ring plate being disposed above the air flow control member;

and

a Z-drive mechanism for adjusting a distance H1 between the ring plate and the air flow control member, the ring plate being vertically movably supported by the Z-drive mechanism.

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12. The liquid processing apparatus of claim 1, further comprising:

an air flow regulation ring including an air inlet
10 having an opening surrounding an outer periphery of the air flow control member, wherein the air inlet communicates with the exhaust unit.

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13. The liquid processing apparatus of claim 12, wherein a top surface of the air flow regulation ring is disposed at a
15 higher position than that of the air flow control member.

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14. The liquid processing apparatus of claim 12, further comprising a plurality of spacers for providing a gap
20 between the spin chuck and the air flow control member.

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15. The liquid processing apparatus of claim 12, wherein a top surface of the air flow control member is substantially at the same level as that of the substrate supported on the
25 spin chuck.

16. The liquid processing apparatus of claim 12, further comprising:

a ring plate for controlling the descending clean air flow towards the substrate supported on the spin chuck, the
5 ring plate being disposed above the air flow control member; and

a Z-drive mechanism for adjusting a distance H2 between the ring plate and the air flow regulation member, the ring plate vertically moving supported by the Z-drive
10 mechanism.

17. A liquid processing method for forming a coating film on a polygonal substrate by spin coating in an ambient with a descending clean air flow, comprising the steps of:

15 (a) supporting the polygonal substrate by a spin chuck and placing at least one air flow control member, which rotates with the spin chuck, along a periphery portion of the substrate except at corner portions thereof;

20 (b) supplying a top surface of the substrate supported on the spin chuck with coating solution and centrifugally spreading the coating solution by rotating the spin chuck about a normal axle;

25 (c) removing a part of the coating solution on the top surface of the substrate by rotating the substrate at a first rotating speed; and

(d) evaporating solvent included in the remaining

coating solution on the top surface of the substrate by rotating the substrate at a second rotating speed slower than the first rotating speed.

5 18. The liquid processing method of claim 17, wherein in the step (a), a transfer arm is lowered relative to the spin chuck, and support extrusions which support corner portions of the substrate are passed through cutout portions of the spin chuck when an area surrounded by the transfer arm is
10 passed through the spin chuck, whereby the substrate is transferred from the transfer arm to the spin chuck.

19. A liquid processing method for forming a coating film on a polygonal substrate by spin coating in an ambient with a
15 descending clean air flow, comprising the steps of:

 (a) supporting the polygonal substrate by a spin chuck and placing at least one air flow control member, which rotates with the spin chuck, along a peripheral portion of the substrate except at corner portions thereof;

20 (b) supplying a top surface of the substrate supported on the spin chuck with coating solution and centrifugally spreading the coating solution by rotating the spin chuck about a normal axle;

25 (c) removing a part of the coating solution on the top surface of the substrate by rotating the substrate at a first rotating speed, after stopping the supplying of the

coating solution is stopped; and

(d) evaporating solvent included in the remaining coating solution on the top surface of the substrate, by rotating the substrate at a second rotating speed slower
5 than the first rotating speed,

wherein, at least in the step (d), in addition to an air flow produced by the rotation of the spin chuck, a horizontally outward air flow is produced from a periphery of the air flow control member.

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20. The liquid processing method of claim 19, wherein at the step (c), a coating solution removed from the substrate during a rotation thereof is drained through a portion below the air flow control member.

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